



A Thermoelectric Temperature Control System w/full control touch screen for the Etch, CVD and PVD process of semiconductor wafer factory helping with the accurate temperature control of the process chamber of Etch or CVD or PVD systems.

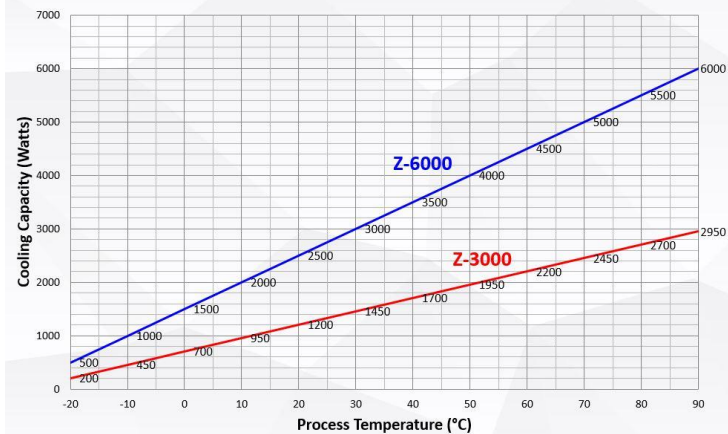
Specification:

Process Circulating Liquid	Fluorinert (FC-3283 3M)
Pump	0.08 kw Magnetically Coupled Pump
Coolant Flow	4 GPM @30psi
Tank	1.5L
Interface Type	RS485C, 232C, Analog DIO, LonWorks, DeviceNet
Rate Current	15A
Rated Voltage	3-phase AC208V±10% 50/60Hz 15A
Dimension	Chiller: H492mm x D460mm x W145mm
	2RU Controller: H125mm x D564mm x W433mm
Weight	Chiller: 25KG ; Controller: 20KG

Advantages:

- Smaller footprint, saving more space.
- No noise.
- Fast temperature response.
- Lower energy consumption. (Energy saving is approx. 80% compared to compressor base chiller)
- Environmentally friendly. (No Freon)
- High reliability. MTBF > 5 years

Cooling Capacity vs. Process Temp.



Specification

Model	Z-3000	Z-6000	Z-6000P
Temp. Control	Range	-20°C~+90°C	-20°C~+90°C
	Accuracy (Idle)	±0.1°C	±0.1°C
	Accuracy (Running)	±1 °C	±1 °C
	Model	PID	PID
Compressor	NA	NA	NA
Refrigerant	Fluorinet (FC-3283 3M)	Fluorinet (FC-3283 3M)	Fluorinet (FC-3283 3M)
Cooling Capacity	1200W@20°C	2400W@20°C	3000W@20°C
Pump	0.08 kw Magnetically-coupled pump	0.08 kw Magnetically-coupled pump	0.08 kw Magnetically-coupled pump
Coolant Flow	4GPM@30psi	4GPM@30psi	5GPM@30psi
Tank	1.5L	3L	3L
Interface Type	RS485/232, Analog DI/O, LonWorks, Device net	RS485/232, Analog DI/O, LonWorks, Device net	RS485/232, Analog DI/O, LonWorks, Device net
Power Consumption	30A	30A	30A
Power Supply	3-phase, AC208V±10%, 50/60Hz	3-phase, AC208V±10%, 50/60Hz	3-phase, AC208V±10%, 50/60Hz
Dimensions	Chiller: H492mm x D460mm x W145mm	Chiller: H492mm x D460mm x W230mm	Chiller: H492mm x D460mm x W230mm
	Controller: H125mm x D564mm x W433mm	Controller: H125mm x D564mm x W433mm	Controller: H125mm x D564mm x W433mm
Weight	Chiller: 25KG	Chiller: 30KG	Chiller: 30KG
	Controller: 20KG	Controller: 25KG	Controller: 25KG

Temp control Accuracy in whole etching process

